

A070052

OC FILE



TENTH QUARTERLY PROGRESS REPORT 1 OCTOBER 1978 TO 31 DECEMBER 1978 CONTRACT DAABO7 - 76 - C - 0041 MANUFACTURING METHODS AND TECHNIQUES FOR MINIATURE HIGH VOLTAGE HYBRID MULTIPLIER MODULES

PLACED BY:

NIGHT VISION AND ELECTRO - OPTICAL LABORATORIES U.S. ARMY ERADCOM, FORT BELVOIR, VA., 22060

CORMO

JUN 181979

CONTRACTOR:

OTTAWA, ONTARIO, CANADA KIA 0S6

SUBCONTRACTOR: ERIE TECHNOLOGICAL PRODUCTS OF CANADA LTD. 5 FRASER AVENUE

TRENTON, ONTARIO, CANADA K8V 551

DISTRIBUTION STATEMENT

79 06 15 09

"APPROVED FOR PUBLIC RELEASE: DISTRIBUTION UNLIMITED"

DISCLAIMER STATEMENT

"The findings in this report are not to be construed as official Department of the Army position unless so designated by other authorized documents."

DISPOSITION INSTRUCTIONS

]

]

]

]]

]

1

"Destroy this report when it is no longer needed. Do not return it to the originator."

ACKNOWLEDGEMENT

"This project has been accomplished as part of the U.S. Army Manufacturing and Technology Program, which has as its objective the timely establishment of manufacturing processes, techniques or equipment to ensure the efficient production of current or future defense programs."

UNCLASSIFIED SECURITY CLASSIFICATION OF THIS PAGE (When Dete E	intered)	
REPORT DOCUMENTATION F	AGE	READ INSTRUCTIONS BEFORE COMPLETING FORM
		3. RECIPIENT'S CATALOG NUMBER
TENTH QUARTERLY REPORT		(9)
A. TITLE (and Subtitle)		5. TYPE OF REPORT & PERIOD COVERED
Manufacturing Methods and Techni	lques /	QUARTERLY Progress re
for Miniature High Voltage Hybri		1 OCTEMPTO-31 DECIDER 78,
Multiplier Modules.		8. PERFORMING ORG. REPORT NUM
7. AUTHOR(a)		8. CONTRACT OR GRANT NUMBER(#)
Contraction and and and and and and and and and an	CET	
B. Grant Gordon P.Eng.	(15)	DAABØ7 - 76 - C - 9941
9. PERFORMING ORGANIZATION NAME AND ADDRESS		10. PROGRAM ELEMENT PROJECT TASK
Erie Technological Products of (anada, Limited	10. PROGRAM ELEMENT, PROJECT, TASK AREA & WORK UNIT NUMBERS
5 Fraser Avenue		Project
TRENTON, Ontario, Canada K8V 5S1		No. 2769766
11. CONTROLLING OFFICE NAME AND ADDRESS	and Flater 2	7 Januar 1979
U.S. Army ERADCOM, Night Vision Optical Laboratories	and Electron St	13. NUMBER OF PAGES
Fort Belvoir, VA., 22060	- Constant	38
14. MONITORING AGENCY NAME & ADDRESS(II different	from Controlling Office)	15. SECURITY CLASS. (of this report)
(1)	41 1	UNCLASSIFIED
-2		15. DECLASSIFICATION/DOWNGRADING
2		SCHEDULE
Approved for Public Release, Dis	tribution Unlimi	ited
Approved for Public Release, Dis		
17. DISTRIBUTION STATEMENT (of the abatract entered in		
17. DISTRIBUTION STATEMENT (of the abatract entered in		
17. DISTRIBUTION STATEMENT (of the abatract entered in		
17. DISTRIBUTION STATEMENT (of the abetract entered in 18. SUPPLEMENTARY NOTES 18. KEY WORDS (Continue on reverse elde if necessary and	n Block 20, 11 different from	n Report)
17. DISTRIBUTION STATEMENT (of the abetract entered in 18. SUPPLEMENTARY NOTES	n Block 20, 11 different from Identify by block number) Voltage Power Sup wes, High Voltage	plies, Night Vision, Second
 DISTRIBUTION STATEMENT (of the abstract entered in 18. SUPPLEMENTARY NOTES 19. KEY WORDS (Continue on reverse elde if necessary and High Voltage Multipliers, High V Generation Image Intensifier Tub Capacitor Banks, Miniature Modul 	n Block 20, il dillerent from Tidentilly by block number) Voltage Power Sup bes, High Voltage	plies, Night Vision, Second
 DISTRIBUTION STATEMENT (of the abstract entered in 18. SUPPLEMENTARY NOTES 19. KEY WORDS (Continue on reverse elde if necessary and High Voltage Multipliers, High V Generation Image Intensifier Tub Capacitor Banks, Miniature Modul 20. WISTRACT (Continue on reverse elde if necessary and 	n Block 20, if different from Identify by block number) Voltage Power Sup bes, High Voltage .es.	pplies, Night Vision, Second Rectifiers, Ceramic
 DISTRIBUTION STATEMENT (of the abstract entered in 18. SUPPLEMENTARY NOTES 19. KEY WORDS (Continue on reverse elde II necessary and High Voltage Multipliers, High V Generation Image Intensifier Tub Capacitor Banks, Miniature Modul 20. JUSTRACT (Continue on reverse elde II necessary and Data is presented on material an multiplier modules. 	n Block 20, 11 dillerent from Identify by block number) Voltage Power Sup bes, High Voltage .es. Identify by block number) ad fixtures used	pplies, Night Vision, Second e Rectifiers, Ceramic in the fabrication of the
 DISTRIBUTION STATEMENT (of the abstract entered in 18. SUPPLEMENTARY NOTES 19. KEY WORDS (Continue on reverse elde if necessary and High Voltage Multipliers, High V Generation Image Intensifier Tub Capacitor Banks, Miniature Modul 20. WISTRACT (Continue on reverse elde if necessary and Data is presented on material and 	n Block 20, 11 dillerent from Identify by block number) Voltage Power Sup bes, High Voltage .es. Identify by block number) ad fixtures used the conductive e	pplies, Night Vision, Second e Rectifiers, Ceramic in the fabrication of the epoxy onto the components
 DISTRIBUTION STATEMENT (of the abstract entered in IS. SUPPLEMENTARY NOTES SUPPLEMENTARY NOTES KEY WORDS (Continue on reverse side if necessary and High Voltage Multipliers, High V Generation Image Intensifier Tub Capacitor Banks, Miniature Modul Distract (Continue on reverse side if necessary and Data is presented on material an multiplier modules. The technique of silk screening 	n Block 20, 11 dillerent from Identify by block number) Voltage Power Sup bes, High Voltage .es. Identify by block number) ad fixtures used the conductive e	pplies, Night Vision, Second e Rectifiers, Ceramic in the fabrication of the epoxy onto the components multiplier.

Π

Π

[

E

I

I

E

E

Π

I

TENTH QUARTERLY PROGRESS REPORT 1 OCTOBER 1978 TO 31 DECEMBER 1978

[]

and the second s

I

I

tes

the second

and a

E

I

I

[]

MANUFACTURING METHODS AND TECHNIQUES FOR MINIATURE HIGH VOLTAGE HYBRID MULTIPLIER MODULES

CONTRACT NO. DAAB07 - 76 - C - 0041

PREPARED BY: B. GRANT GORDON, P.ENG.

DISTRIBUTION STATEMENT

"APPROVED FOR PUBLIC RELEASE: DISTRIBUTION UNLIMITED"

NTIS DDC	Giuici I
	iounced
Justi	fication
By	
Distr	ibution/
Avai	lability Codes
	Avail and/or
Dist	special

ABSTRACT

The progress made during the tenth quarter of work on the Manufacturing and Technology Programme for Miniature High Voltage Multiplier Modules is described in this report.

E

E

I

Γ

[

L

Data is presented on material and fixtures used in the fabrication of the multiplier modules.

The technique of silk screening the conductive epoxy onto the components is described in the fabrication of the voltage multipliers.

i

TABLE OF CONTENTS

[]

]

I

	PAGE
ABSTRACT	i
LIST OF TABLES	111
LIST OF ILLUSTRATIONS	iii
PURPOSE	iv
GLOSSARY OF SPECIAL TERMS	v
LIST OF SYMBOLS AND ABBREVIATIONS	vii
1. INTRODUCTION	1
2. FABRICATION AND EVALUATION OF MULTIPLIERS	4
3. CONCLUSIONS	11
4. PROGRAMME FOR NEXT QUARTER	12
5. PUBLICATIONS AND REPORTS	12
6. IDENTIFICATION OF PERSONNEL	13
APPENDIX A. DISTRIBUTION LIST	

LIST OF TABLES

[]

Π

 Π

- and

[

-

[]

[]

[]

[]

[]

TABLE		PAGE
1.	Electrical Test Data for TSK-25-260 Curved Capacitor Banks	14
2.	Mechanical Inspection Data for TSK-25-260 Capacitor Banks	15
3.	Output Voltage of Multipliers using TSK-25-260 Capacitors and HV30P Diodes	19

LIST OF ILLUSTRATIONS

FIGURE		PAGE
1.	Electrode Pattern Dimensions of TSK-25-260 Capacitor (Sample A)	16
2.	Electrode Pattern Dimensions of TSK-25-260 Capacitor (Sample B)	17
3.	Dimensioning of Curved Bank Capacitors TSK-25-260	18
4.	Rectangular Substrate Plate, TSK-312-104 'B'	20
5.	Curved Substrate Plate, TSK-313-104 'B'	21
6.	Rectangular Multiplier Fixture, TEX-109-302 'A'	22
7.	Epoxy Silk Screen (Curved Bank Multiplier), TSK-313-105	23

PURPOSE

This Contract covers component designs, mounting and interconnection techniques, tooling and test methods and other manufacturing methods and techniques required for production of rectangular and curved miniature high voltage multiplier modules. These units are to be used in low cost power supplies for image intensifier tubes. The full scope and details of the specification are given in Appendix A to the Eighth Quarterly Report.

Major milestones in this program consist of delivery of the following items:

- (1) First and second engineering samples and test data.
- (2) Production line layout and schedule.
- (3) Confirmatory samples and test data.
- (4) Production line set-up.
- (5) Pilot production run.
- (6) Production rate demonstration.
- (7) Preparation and publication of a final report.

The general approach is to design and set-up a cost-effective production capability, utilizing already established device technologies and materials, and to demonstrate the production line capability to fabricate at the rate of 125 acceptable units per 40 hour week.

iv

GLOSSARY OF SPECIAL TERMS

Capacitor bank: - Ceramic wafer with metallizations which perform the function of a number of capacitors connected in parallel (parallel bank) or in series (series capacitor bank).

- Cure: To change the physical properties of a material by chemical reaction or by the action of heat and catalyst.
- Flash test: Test consisting of instantaneous application
 of voltage at its specified value to the
 part.
- Hybrid: Technology combining thick-films (capacitor banks) with discrete devices (rectifiers).

Multiplier Modules:

Pad:

voltage multiplication and rectification. - The metallized area on the ceramic bank acting as a plate of a capacitor and used

- Device consisting of capacitor banks and

rectifiers connected and packaged to perform

Rectifier:

- Semiconductor device with one or more p-n junctions connected in series.

to make an electrical connection to it.

Rectifiersubstrate Assembly: - A substrate with rectifiers placed and secured within it.

v

Substrate:

- Part of a multiplier module consisting of a piece of insulating material machined to accommodate the rectifiers and support the capacitor banks. 0

LIST OF SYMBOLS AND ABBREVIATIONS

ic	-	charging current (µA)
° _x	-	measured capacitance (pF)
D.F.	-	dissipation factor (%)
f	-	frequency (KHz)
c _i	-	input capacitance (pF)
IL	-	load current (nA)
vr	-	ripple voltage (V)
v _B	-	breakdown voltage (V)
Vi	-	input voltage (Vp-p)
vo	-	output voltage (V d.c.)
η	-	efficiency (%)
v _F	-	rectifier forward voltage drop (V)
PTRV	-	peak transient reverse voltage (V)
IR	-	rectifier leakage current (nA)

Π

Ι

Π

I

T-

E.

in the second

-

Π

[]

Π

[]

[]

Π

t startes k vii

1. INTRODUCTION

Γ

Γ

I

This report describes briefly the progress in the Manufacturing Methods and Techniques for Miniature High Voltage Hybrid Multiplier Modules Program, made during the latest calendar quarter.

In the First Quarterly Report the design and the manufacturing process for rectangular and curved multiplier modules were described. Prototype rectifier-substrate assemblies were fabricated and then redesigned to simplify the assembly operation. The specification covering the requirements for the multiplier modules forms Appendix A of the Report.

In the Second Quarterly Report results of the electrical evaluation of the first sample batch of rectangular capacitor banks TSK 25-250 and TSK 25-251 were given, the choice of the rectifier was made and electrical test results were presented on non-modular multipliers fabricated with TSK 25-250 and TSK 25-251 capacitor banks and standard HV20PD four-junction rectifiers, to evaluate these components.

In the Third Quarterly Report results of electrical tests on rectangular multiplier modules were presented.

For an input voltage of 1 KV, efficiencies above 96% under no-load conditions and above 95% with 500 nA load currents were achieved for all multipliers assembled with TSK 25-250 and TSK 25-251 and three-chip rectifiers. Low ripple voltages, input capacitances and charging currents were also measured on these multipliers. Results of the mechanical and electrical evaluation of TSK 25-249 curved capacitor banks were also presented in the Third Quarterly Report.

In the Fourth Quarterly Report work on impregnation and coating of the multipliers was discussed as well as some problems associated with the fabrication of the rectifiersubstrate assemblies. The fabrication of rectangular and curved multipliers for the First Engineering Sample was discussed.

In the Fifth Quarterly Report were presented the results of electrical performance testing at the room, high $(+52^{\circ}C)$ and low $(-54^{\circ}C)$ temperatures, as well as effects of thermal shock, and high and low temperature storage.

In the Sixth and Seventh Quarterly Reports were presented the results of testing of rectangular and curved multipliers to the Second Engineering Sample requirements,

steps to improve the frequency performance of the multipliers and optimization of the rectifiers for these devices, as well as results of life testing of multipliers.

-

[]

l

[]

[]

[]

In the Eighth Quarterly Report the results of the reliability testing of rectangular and curved multipliers to the Second Engineering Sample requirements were analyzed and further steps to improve the performance of the multipliers and optimize the rectifiers for these devices were discussed.

In the Ninth Quarterly Report the results of further lifetesting of rectangular and curved multipliers was discussed. The commencement of the Confirmatory Sample phase was described including improvements in the manufacturing methods.

2. FABRICATION AND EVALUATION OF MULTIPLIERS

2.1 Substrate Assembly

The first batch of 38 substrate assemblies experienced manufacturing difficulties and were rejected. The 20 rectangular assemblies were correctly assembled manually (as per Engineering Samples) but all exhibited some faults. Each unit had several rectifiers in it (after processing) which did not meet the specifications on forward voltage drop (V_F) , peak transient reverse voltage (PTRV) and/or leakage current (IR). The failures were characterized by a V_F that was either very resistive or open, a PTRV of less than 1000 volts or an I_R of greater than 100 nA. (Specified values are 2.5 to 4.5V for V_F at 10 mA, 1500 Vpp minimum for PTRV and 7 nA maximum for I_R at 1000V bias.) A failure analysis on these substrates showed two problems: an overlapping of the substrates and a number of voids in the encapsulating epoxy. The overlapping condition exposed the silicon of some rectifiers and caused improper contact, thus, giving high values for $V_{\rm F}$. The epoxy voids caused "arc-over" at the PTRV test and allowed a high I_R due to the exposed surface between anode and cathode.

The 18 curved substrates were incorrectly assembled (i.e. all the rectifiers were reversed), as the

result of an operator error. They were examined anyway and exhibited essentially the same problems as the rectangular units: overlapping and epoxy voids.

Then a second batch of 40 substrates was assembled; 20 rectangular and 20 curved types. More control was exercised on this lot and the results were far better although there were several reversed diodes and some overlapping of the substrates. Therefore, we started a batch of 20 voltage multipliers - 10 of each type. Unfortunately all 20 parts failed at the first inspection on V_F . All but 1 of the assemblies were "open" although 2 had continuity at the correct value but in the wrong polarity and a third unit had a low value of V_F indicating a short of one or more diodes in the substrate. A failure analysis showed the major problem to be excessive conductive epoxy at the substrate lead slots and since this is cured in advance of the assembly operation, the excess prevented the DC capacitor from making proper contact with the substrates. The curved multipliers had an additional problem in that the substrates were placed in the "sandwich" configuration backwards so that the ${\rm V}_{\rm F}$ was reversed from the correct value - another operator error.

-

5.

These 20 parts were reworked however we only achieved 1 working unit (curved) while 18 of the others were either "open" or "shorted" and 1 unit had a low V_F - indicative of a short of one or more diodes on the substrate assembly.

A failure analysis of these parts showed two problems: epoxy build-up at the slots (as had happened on the original manufacture) and epoxy "smearing" on the contacting surfaces so that "bridges" or "shorts" were created. Meanwhile another group of 80 substrate assemblies (40 of each type) were then fabricated. We achieved much better results, especially on the last batch of 40 parts for which we had de-aired the encapsulating epoxy prior to use in addition to the normal vacuum de-airing during the potting of the substrates.

Due to our previous problems with the multiplier manufacture using manual assembly, we investigated several alternatives and decided upon a silk screen technique as our most feasible approach. The basic idea is relatively simple as it is merely the application of a thin layer of the Epo-Tek epoxy (less than .001") onto both the ceramic capacitors and the

rectifier-substrate assembly. This entails that 4 layers of epoxy are deposited on the various surfaces; two of which can use the same screen that the Ceramic group uses for printing the electrode pattern on the capacitor itself and the other two of which require a screen which is the mirror image of the first one. We have proved that the silk screen technique will work insofar as a controlled deposition of epoxy in a specified location is concerned and we now require the second screen to complete our evaluations. The various screens were placed on order with Erie, Pa. and received at the end of December. In addition a fixture was designed to hold the various components in place by use of a vacuum while the epoxy is being silk screened onto its surface. The fixture was built in our model shop and proved on our capacitors and substrates. The silk screen procedure and holding fixture are illustrated in Fig. 7.

I

1

-

-

Further, the fixture for holding the rectangular substrates during loading and encapsulating of the diodes has been modified slightly to include a baseplate (for better stability) and an improved cavity

outline (to allow easier unloading of the cured substrate assemblies). The fixture is illustrated in Fig. 6.

2.2 Production Materials

As sufficient rectifiers had been fabricated with the thin nailhead lead (HVRO4M-13) without problems, I released the remaining 50,000 pieces of the order to Emporium Specialties for this part with a scheduled delivery of early January 1979.

By the end of December we had received 2640 rectifiers (type HSC-3, part number RD0058). These devices are now being stockpiled for later use in the Confirmatory Sample and Pilot Production Run.

The substrate plates (P/N TSK-312-104 and TSK-313-104) have been modified slightly for ease of manufacture (see Fig. 4 and 5) and RFQ's were sent out to several vendors including the manufacturer of the Vespel SP-1 polyimide, Dupont. We should receive their responses in the early part of the new year and, if satisfactory, we will place an order for sufficient parts to cover the Pilot Production Run.

We have received the first batch of capacitors, P/N TSK-25-260 (lot #850066), manufactured by the Erie Trenton Ceramic Production Group. The electrical measurements are given in Table 1 and the mechanical characteristics in Table 2 and Fig. 1, 2 and 3.

In general the capacity is higher and the breakdown voltage lower compared to capacitors supplied by Erie, Pa. The ceramic engineers involved in this project have assured me that the V_B can be increased and we should see higher readings on the next parts supplied to us.

Mechanically, the samples do not meet all the print dimensions in several areas especially the bank thickness, total arc length and electrode pattern screening. Sample B was an example of a mis-screened capacitor and the entire lot had to be sorted for correct registration of the electrode pattern. Therefore the number of acceptable capacitors amounted to 219 pieces. The ceramic engineers have indicated that they will work on improving the dimensions for the next batch of capacitors to be delivered.

9

An additional test was performed on the capacitors to check the dielectric qualities of the ceramic: 10 capacitors were fabricated into 5 voltage multipliers of a standard (rather than miniature) configuration using a regular Erie diode, HV30P. These parts were tested in Fluorinert dielectric fluid and the results are listed in Table 3. These results show a very good efficiency and breakdown voltage on all multipliers.

3. CONCLUSIONS

- and

I

I

[]

Π

The material problems are being solved and the appropriate quantities of components to complete the Pilot Production Run are in manufacture or on order from outside vendors with the exception of the substrates which are out on RFQ's at this time.

The technique of silk screening epoxy onto the components as part of the fabrication of the voltage multipliers appears to be a feasible one and will be utilized in further investigation.

4. PROGRAMME FOR NEXT QUARTER

- 4.1 Ascertain the validity and usefulness of the silk screen procedure.
- 4.2 Initiate manufacture of confirmatory sample voltage multiplier modules.
- 4.3 Commence testing on confirmatory sample multipliers.

5. PUBLICATIONS AND REPORTS

No reports or publications were made on the work associated with this program during the current quarter.

6. IDENTIFICATION OF PERSONNEL

Ш

-

I

I

T

1

[]

1

1

0

1

Brief descriptions of the background of technical personnel involved were included in the preceding Quarterly Progress Reports.

During the Ninth quarter of the program the following persons worked in their area of responsibility:

INDIVIDUAL	RESPONSIBILITY	HRS. SPENT
B.G. Gordon	Programme Manager	158
D. Platt	Manager, Quality Assurance and Control, High Voltage Products	1
D. Archard	Senior Test Technician	4
K. Cram	Draughtsman	2
V. Glenn	Q.C. Inspector	12
C. Grills	Senior Engineering Technician	72.5
B. Heidt	Process Engineering Supervisor	4
L. Macklin	Draughtsman	13
P. Maples	Senior Engineering Technician	48
D. Regan	Senior Engineering Technician	16
F. Treverton	Senior Test Technician	3
	Manufacturing Personnel	141.1
TOTAL HOURS -	in quarter	474.6
TOTAL HOURS -	to date	4854.0

ELECTRICAL TEST DATA FOR TSK - 25 - 260 CURVED CAPACITOR BANK SAMPLES LOT # 850066

-

]

]

-

New Joy

Name.

-

]

]

1

]

UNIT #	PAD #	С _Х @ О КV (рF)	D.F. (%)	С _Х @ 6 КV (рF)	v _в (кv)
A	1 2 3 4 5 6	99.3 100.8 101.7 100.6 99.1 100.1	$ 1.55 \\ 1.36 \\ 1.53 \\ 1.28 \\ 1.61 \\ 1.43 $	69.5 70.6 71.2 70.4 69.4 70.1	10.8 7.7 8.6 7.7 8.9 7.5
В	1 2 3 4 5 6	103.4 111.8 110.0 107.9 117.0 109.1	1.50 1.18 1.24 1.31 1.14 1.17	72.4 78.3 77.0 75.5 81.9 76.4	9.0 8.7 9.0 7.9 7.7 7.9
с	1 2 3 4 5 6	102.0 106.3 113.9 110.1 109.3 103.0	.87 .87 .81 .80 .81 .79	71.4 74.4 79.7 77.1 76.5 72.1	9.5 9.2 9.0 8.2 9.0 9.0
Ave	erage	105.9	1.18	74.1	8.6

TABLE 1

			UN	IT # A			
PAD #		1	2	3	4	5	6
A B C D E F G H J	.2517 .0476 .0206 .0887	.0393 .0433 .0504 .0463 .0223	.0403 .0422 .0496 .0502 .0237	.0392 .0412 .0472 .0464 .0223	.0415 .0424 .0481 .0455 .0227	.0427 .0384 .0506 .0473 .0233	.0441 .0401 .0472 .0463 .0233
			10.	IT # B			
PAD #		1	2	3	4	5	6
A B C D F G H J	.2465 .0423 .0220 .1085	.0730 .0233 .0458 .0446 .0202	.0574 .0360 .0453 .0443 .0201	.0443 .0503 .0435 .0440 .0205	.0307 .0644 .0439 .0435 .0199	.0174 .0778 .0427 .0443 .0193	.0085 .0878 .0436 .0441 .0187

MECHANICAL INSPECTION DATA FOR TSK-25-260 CAPACITOR BANKS LOT # 850066

Notes: (i) All dimensions in inches. (ii) See Fig. 3 for dimensioning.

[]

-

I

Π

[]

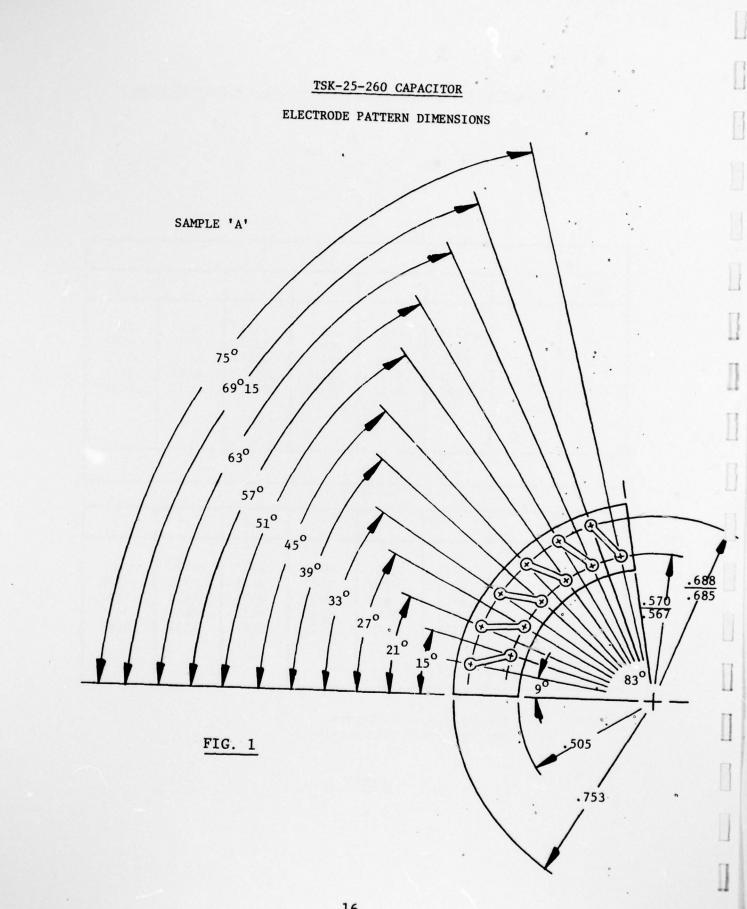
[]

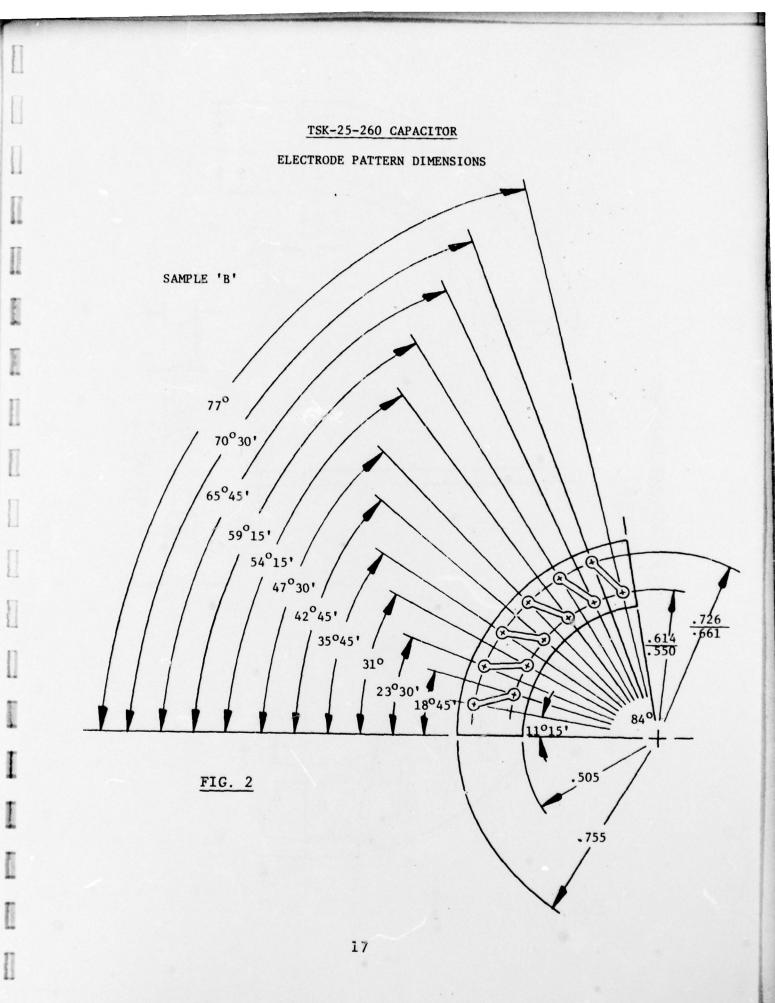
[]

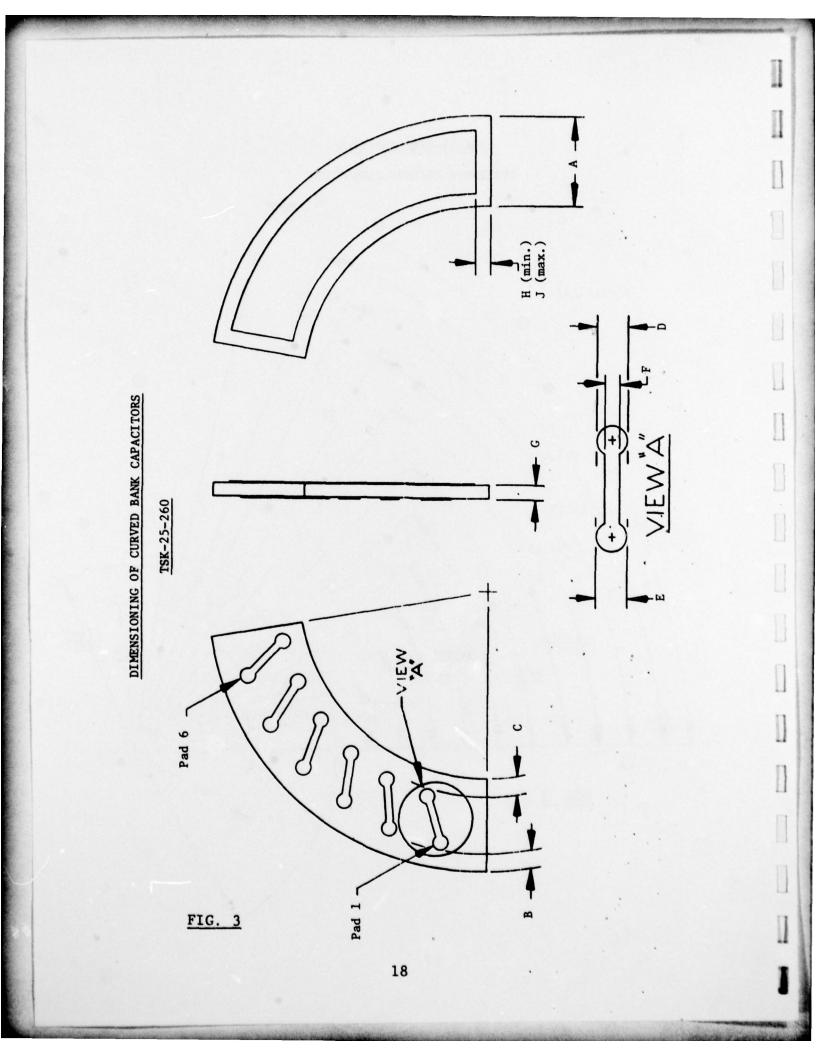
[]

a an experimental available of

TABLE 2







OUTPUT VOLTAGE OF MULTIPLIERS USING TSK-25-260 CAPACITORS (LOT # 850066) AND HV30P DIODES

$v_i (v_{pp})$	1000	1150	1 300	Breakdown
UNIT #				(iii)
29	6.0KV	6.95KV	7.95KV	9.4KV
30	6.0	6.95	7.95	10.3
31	6.0	6.95	7.95	9.3
32	6.0	6.95	7.95	8.0
33	6.0	6.95	7.95	9.4

Notes:

.

-

I

I

trat

[]

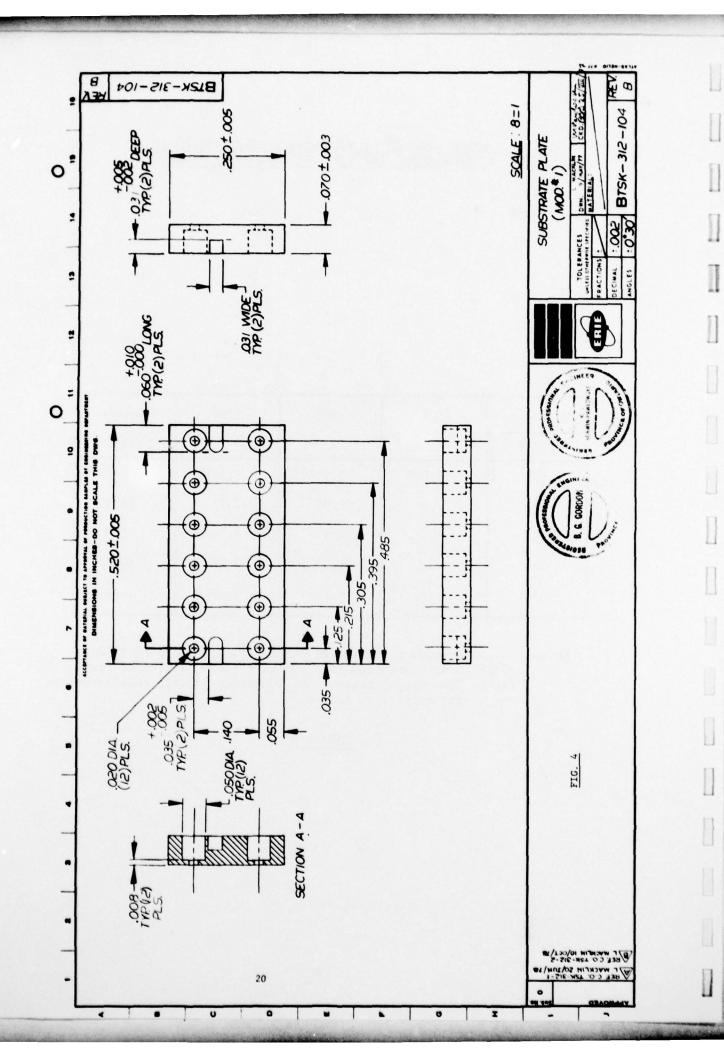
0

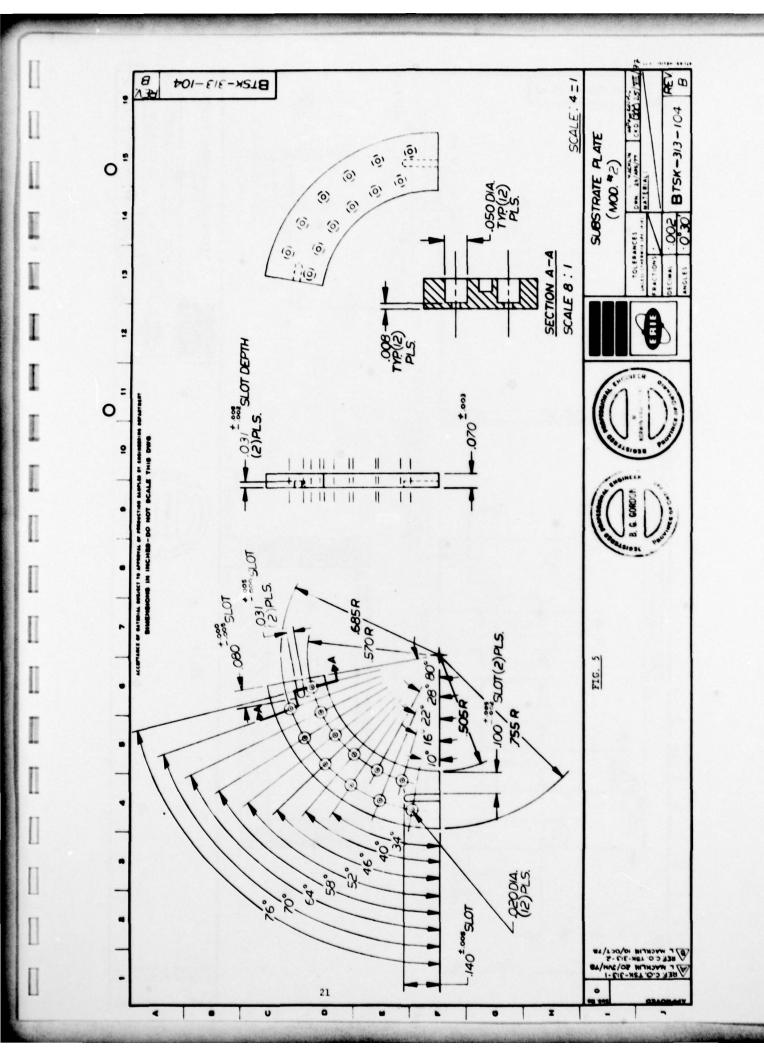
(i) Frequency of applied voltage in all tests is 35 KHz.

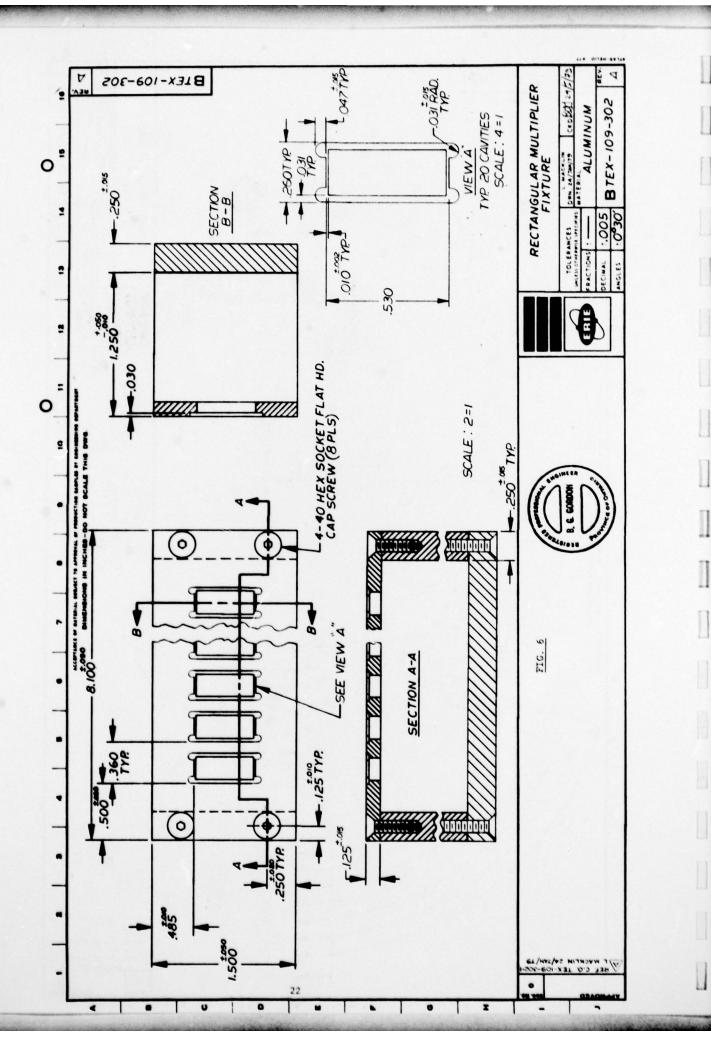
(ii) Tests conducted in Fluorinert FC-43 dielectric fluid.

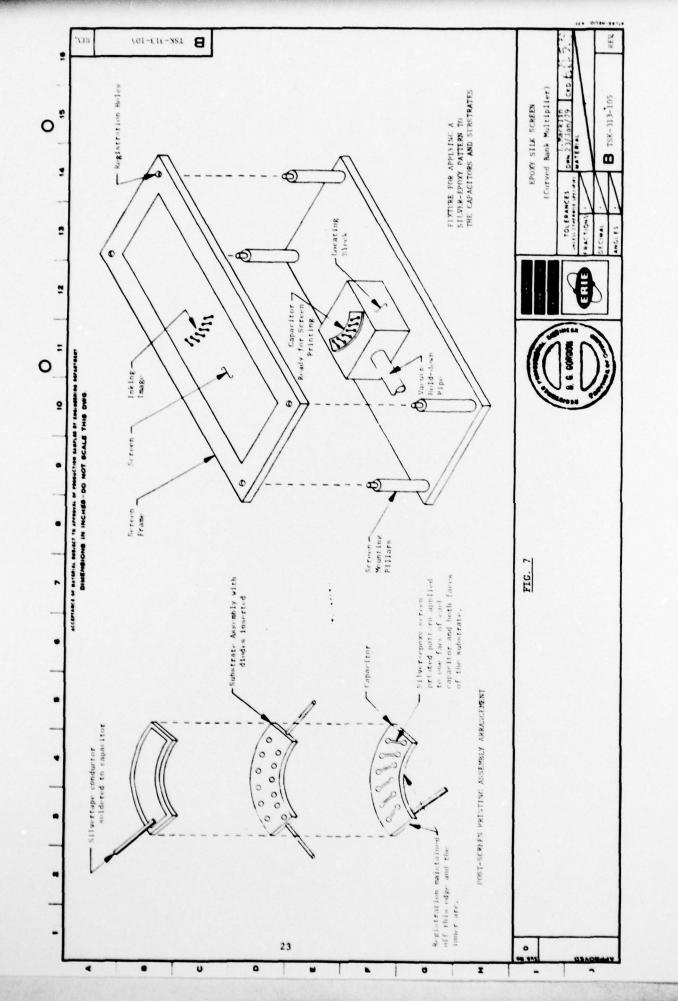
(iii) "Breakdown" denotes the DC output voltage reached before the multiplier failed.

TABLE 3









-

I

DISTRIBUTION LIST

Π

Π

Π

DISINISOTIAN HIST	
ADDRESS	COPIES
Commander U.S. Army ERADCOM Night Vision and Electro-Optical Laboratories ATIN: DELNV - S1 (Mr. J. Evans) Ft. Belvoir, VA. 22060	3
Director ATIN: DRSEL - RD - EV (Mr. Soo Young Shin) Fort Belvoir, VA. 22060	1
Commander U.S. Army Production Equipment Agency ATTN: AMXPE - MT (Mr. C.E. McBurney) Rock Island, IL. 61201	1
I.T.T. Electron Tube Division ATIN: Mr. A. Hoover Post Office Box 7065 Roanoke, VA. 24019	1
Ni-Tec Night Vision Technology Corporation ATIN: Mr. Ferd Fender 7426 Linder Avenue Skokie, IL. 60076	1
RCA Main Plant Electronics Components Division ATIN: Mr. Richard Mangen New Holland Avenue Lancaster, PA. 17604	1
Varo, Incorporated ATIN: D. Lipke 2203 Walnut Street Garland, Texas 75040	2
Galileo Electro Optics Corporation ATIN: J. Zaghi Galileo Park Sturbridge, Massachusetts 01518	2
Channel Products Incorporated ATIN: Mr. D. Berlincount 16722 Park Circle Drive, West Chargrin Falls, Ohio	1

ADDRESS	COPIES
Venus Scientific ATIN: Mr. F. Galluppi 399 Smith Street Farmingdale, N.Y. 11735	1
L & K Industries ATIN: Mr. L. Kastner 3579 Merrick Road Seaford, Long Island, N.Y. 11783	1
Gulton Industries Piezo Products Division ATIN: Mr. D. Herzfeld Box 4300 Fullerton, CA 92634	1
K & M Electronics 59 Interstate Drive West Springfield, Massachusetts 01089	1
Defense Documentation Center ATIN: DDC - IRS Cameron Station Building 5 Alexandria, VA 22314	12
Honeywell, Incorporated Government and Aeronautical Products Division Ceramics Center Golden Valley, Minnesota 55422	1
Director National Security Agency ATIN: TDL Fort George G. Meade, MD 20755	1
Office of Naval Research Code 427 Arlington, VA 2217	1
Air Force Avionics Lab ATTN: AFAL/DOT, STINFO Wright-Patterson AFB, OH 45433	1
Ofc., Asst. Sec. of the Army (R&D) ATIN: Asst. for Research Room 3 - E - 379, the Pentagon Washington, DC 20310	1
Masiningcon, bo 20010	

ADDRESS	COPIES
Commanding General U.S. Army Research & Development Command ATTN: DRCMT 5001 Eisenhower Blvd. Alexandria, VA 22233	1
C.G., U.S. Army Missile Command Redstone Scientific Infor. Ctr. ATTN: Chief Document Sect. Redstone Arsenal, AL 35809	1
Reliability Analysis Center RADC (RBRAC) ATTN: I.L. Krulac Griffiss AFB, N.Y. 13441	1
Director Night Vision Lab. ECOM ATTN: DRSEL - NV - II Mr. Joseph Martino Ft. Belvoir, VA 22060	1
Commander Air Force Avionics Lab AVIM ATIN: Dr. Ronald Belt Wright-Patterson AFB, OH 45433	1
Bell Northern Research ATIN: Technical Library P.O. Box 3511, Station C Ottawa, Ontario, Canada	1
Fairchild Semiconductor Research & Development Laboratory ATIN: Dr. James M. Early 4001 Miranda Avenue Palo Alto, CA 10504	1
General Electric Research & Development Center ATIN: Dr. J.J. Tiemann Schenectady, N.Y. 12305	1
Naval Research Lab. ATTN: Dr. David F. Barbe (Code 5260) 4555 Overlook Avenue Washington, DC 20375	1
Mr. W.H. Dodson Sandia Laboratories Div., 2116 Albuquerque, N.M. 87115	1

Π [] R R 8 0

A-3

ADDRESS COPIES Carmine J. Salvo 1 Rome Air Development Ctr. Griffiss AFB, N.Y. 13441 Dr. Barry Dunbridge 1 TRW Systems Group One Space Park Redondo Beach, CA 90278 AFAL/TEA 1 ATTN: Fritz Schuermeyer Wright-Patterson AFB, OH 54433 Naval Ordnance Lab. 1 ATIN: Mr. Frederick E. Warnock White Oak, MA 20910 Dr. H.A.R. Wegener 1 Sperry Rand Research Center Sudbury, MA 01776 Mr. James Doyle 1 General Electric Defense Electronics Division Utica, N.Y. 13503 Mr. F.B. Micheletti 1 Electronics Research Division Rockwell International 3370 Miraloma Avenue Anaheim, CA 92803 Dr. Andrew Ticki 1 Nitron Corporation 10420 Bubb Road Cupertino, CA 95014 Commander 1 RADC ATIN: RBRM/Mr. J. Brauer Griffiss AFB, N.Y. 13441 Dr. Gerald B. Herzog 1 Solid-State Technology Center RCA David Samoff Research Ctr. Princeton, N.J. 08540 Dr. George E. Smith 1 Bell Telephone Laboratories, Inc.

A-4

Room 2A - 323

Murray Hill, N.J. 07974

DDRESS

Π

Π

I

E

Π

I

[]

[]

the second s

ADDRESS	
Director	1
Defense Communications Agency Technical Library Center Code 205 (P.A. Tolovi) Washington, DC 20305	
Institute of Defense Analysis Arlington, VA 22209	1
Dr. Gordon E. Moore Intel Corporation 3065 Bowers Road Santa Clara, CA 95951	1
Commander Harry Diamond Laboratories ATTN: Mr. A.J. Baba 2800 Powder Mill Road Adelphi, MD 20783	1
Naval Electronic Laboratory Ctr. ATTN: Mr. C.E. Holland, Jr. (Code 4300) 271 Catalina Blvd. San Diego, CA 92152	1
Mr. R. Weglein Hughes Research Laboratories 3011 Malibu Canyon Road Malibu, CA 09265	1
Sperry Rand Research Center 100 North Road Sudbury, MA 01776 ATTN: Dr. H. Van De Vaart	1
Westinghouse Electric Corp. Research & Development Center Beulah Road Pittsburgh, PA 15235	1
Stanford Research Institute Menlo Park, CA 94025 ATIN: Dr. A. Bahr	1
00, USA Foreign Science Div. ATTN: AMXST CE Division 220 Seventh St. NE Charlottesville, VA 22901	1

COPIES

ADDRESS

U.S. Army Research Office-Durham ATIN: CRDARD-IP Box CM, Duke Station Durham, N.C. 27706

U.S. Army Research Ofc-Durham ATIN: Dr. Robert J. Lontz Box CM, Duke Station Durham, N.C. 27706

USA Security Agency ATIN: LARD Arlington Hall Station, Bldg 420 Arlington, VA 2212

Director U.S. Army Adv Matl Concepts Agency ATIN: AMXAM Washington, D.C. 20315

Commanding General U.S. Army Missile Command ATIN: DRSMI-RFG (Mr. N. Bell) Redstone Arsenal, AL 35809

Commanding Officer Harry Diamond Laboratories ATTN: DRXDO-RCB (Mr. Nemarich) Washington, D.C. 20438

Commanding Officer USA Satellite Comm Agency ATTN: DRCPM-SC-3 Fort Monmouth, N.J. 07703

U.S. Army Liaison Office MIL-Lincoln Lab, Room A-210 P.O. Box 73 Lexington, MA 02173

Chief, Intell Matl Dev Office Electronic Warfare Lab, ECOM Fort Holabird, MD 21219

Erie Technological Products of Canada Limited 5 Fraser Avenue Trenton, Ontario K8V 5S1 ATTN: Mr. Brian McCallum COPIES

1

1

1

1

1

1

1

1

1

ADDRESS

T

1

11

I

1

I

Π

[

I

Г

I

Advisory Gp on Electron Devices 201 Varick St. 9th Floor New York, N.Y. 10014

U.S. Army Electronics Command Chief-Intelligence Material Development Office Electronic Warfare Laboratories Fort Holabird, MD 21219

National Semiconductors Ltd. ATIN: Dr. M. Korwin-Pawlowski 2150 Ward St. Montreal, Quebec Canada, HYM 1T7 1